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Contents

v Conference Committee

| | DI ACADONIC MATERIALS AND MANOSTRUCTURES I |
|----------|--|
| | PLASMONIC MATERIALS AND NANOSTRUCTURES I |
| 13111 02 | Tunable electro-optic resonant metasurfaces (Invited Paper) [13111-14] |
| | |
| | PLASMONIC APPLICATIONS I |
| 13111 03 | Metasurface perfect absorbers for light control: beyond visible and infrared emitters (Invited Paper) [13111-23] |
| | |
| | FUNDAMENTAL OF PLASMONICS II |
| 13111 04 | Emission modification of Sm³+ doped glass due to plasmon effect [13111-17] |
| | |
| | METASURFACES IV |
| | |
| 13111 05 | Metasurface-based depth sensing and topology optimized high-Q metasurfaces (Invited Paper) [13111-33] |
| | |
| | PLASMONIC MATERIALS AND NANOSTRUCTURES III |
| 13111 06 | Plasmonic nano-disks arrays made with electron beam lithography using the dots-on-the-fly method [13111-49] |
| | |
| - | METASURFACES VI |
| 13111 07 | An unconventional take on plasmonic metasurfaces (Invited Paper) [13111-55] |
| | |
| | PLASMONIC MATERIALS AND NANOSTRUCTURES V |
| 13111 08 | Self-organization via 3D printing of anisotropic plasmonic structures [13111-65] |
| 12111 00 | |
| 13111 09 | Plasmon effect provides emission stabilization of glass matrices under high temperature [13111-66] |
| | |

POSTER SESSION

| 13111 0A | Methodology for robust process window discovery in plasmonic nanostructures [13111-72] |
|----------|---|
| 13111 OB | High-efficiency plasmonic filter-based microlens array for multispectral infrared sensor [13111-74] |
| 13111 0C | Effects of defocusing on near-field intensity enhancement [13111-76] |

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